

Please amend the following claims as indicated:

1. (Amended) A chrome plated part comprising a substrate having a crack-free chrome layer on a surface thereof, the crack-free chrome layer having compressive residual stress of 100 MPa or more and being formed by electroplating.

A6 2. (Amended) A chrome plated part comprising a substrate having a crack-free chrome layer on a surface thereof, the crack-free chrome layer having compressive residual stress of 150 MPa or more and being formed by electroplating.

10 9 3. (Amended) A chrome plated part according to claim 2, wherein the crack-free chrome layer has a crystal grain size of 9 nm or more.

4 5. (Amended) A chrome plated part according to claim 1, wherein the crack-free chrome layer is a lower chrome layer and the chrome plated part further comprises a cracked upper chrome layer which is formed on the lower chrome layer by electroplating.

A7 7 4 6. (Amended) A chrome plated part according to claim 5, further comprising at least one intermediate chrome layer which is formed between the lower chrome layer and the upper chrome layer by electroplating.

14 8. (Amended) A chrome plating method comprising the step of conducting electroplating of a work in a chrome plating bath by application of a pulse current, the chrome plating bath containing organic sulfonic acid, to thereby deposit a crack-free chrome layer on a surface of the work, the crack-free chrome layer having compressive residual stress of 100 MPa or more.

A8 13 9. (Amended) A chrome plating method comprising the step of conducting electroplating of a work in a chrome plating bath by application of a pulse current, the chrome plating bath containing organic sulfonic acid, to thereby deposit a crack-free chrome layer on a surface of the work, the crack-free chrome layer having compressive residual stress of 150 MPa or more.